

# caeleste



## **CCD and CMOS: A journey through the past and the future**

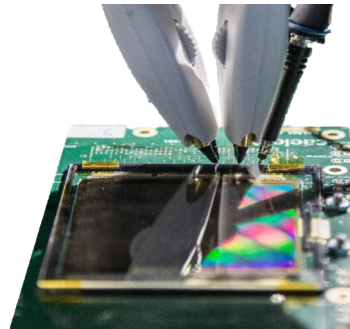
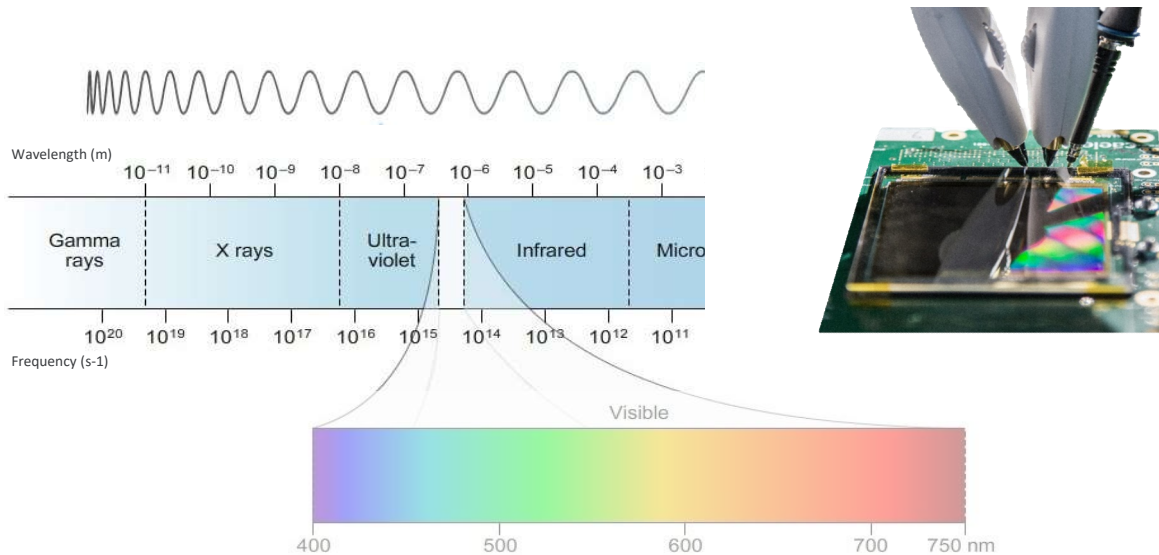
Ben De Brabanter, Jeroen Hoet, Jan Vermeiren

Caeleste, Belgium



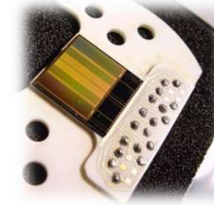
- Caeleste company introduction
- The Historical track: towards CCD
- The Present and the future: CMOS and the application broadening

# Caeleste's mission



Be the supplier of beyond state-of-the-art  
custom-designed CMOS image sensors

## Imaging the ...

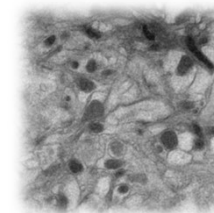


... very far away

Mass spectrometer of the ROSINA/DFMS  
Today resting on the surface of Comet  
67P/Churyumov-Gerasimenko

... very large

4096 x 4096 pixels  
70mm sensor diagonal



... very small

Fly neuron  
8k x 8k TEM

... invisible

Color X-ray of breast  
cancer





## Stable growth

Founded in 2006  
Owned by founders & employees  
20% CAGR<sub>15-20</sub>



## Expertise

45+ Employees  
13+ nationalities  
12+ tape-outs per year



## Collaboration

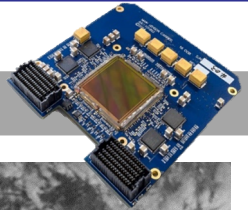
University collaboration  
100+ peer reviewed publications  
Caeleste University



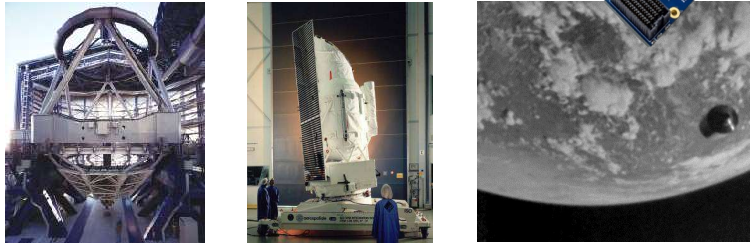
## Technology

15 patents granted  
2 patents pending

# Expertise in different applications



## Scientific & Space

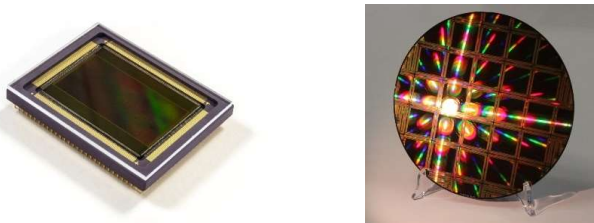


## Medical & Life science



Caeleste's  
Unique custom-design  
Experience

## Industrial applications



## Trusted partner for our customers



+ many more



- Caeleste company introduction

- The Historical track: towards CCD

- Why imaging
- The CCD precursors
- The CCD era
- The CCD limitations

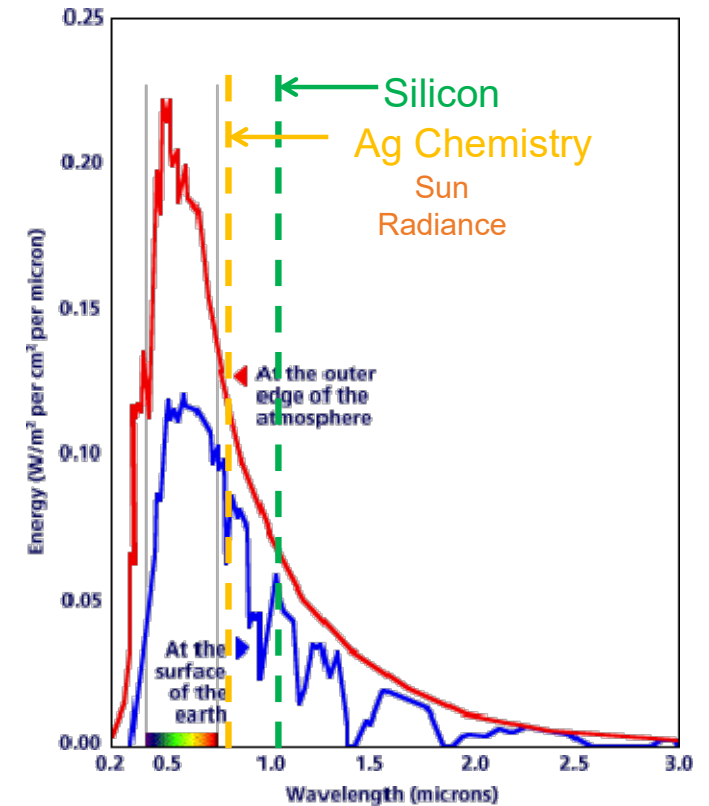
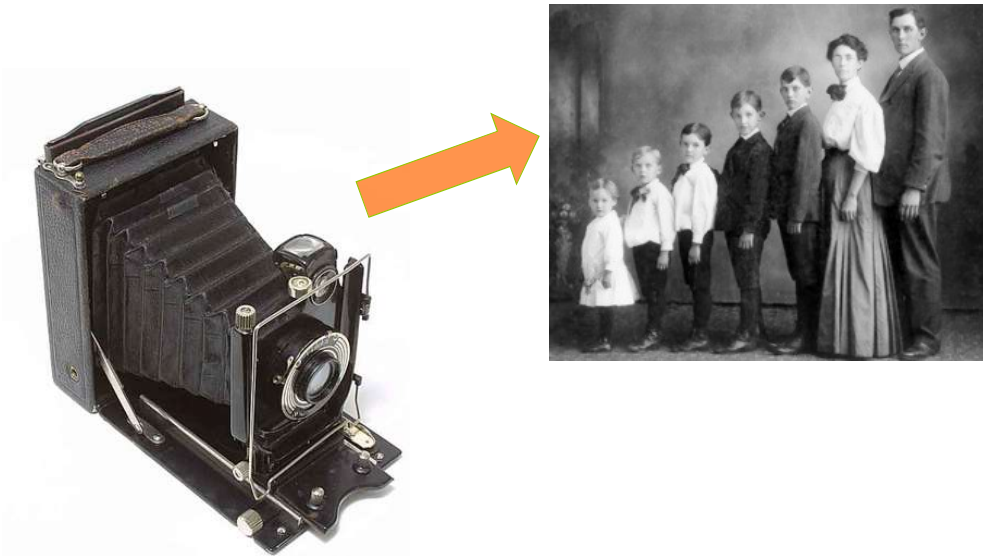
- The Present and the future: CMOS and the application broadening

# Humans want to preserve



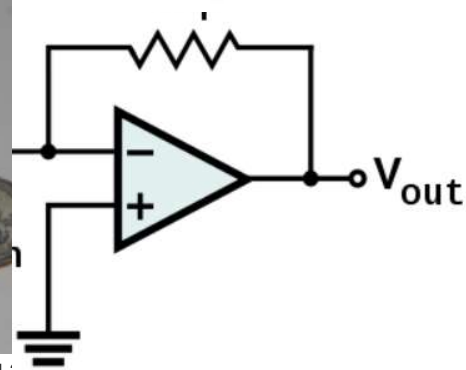
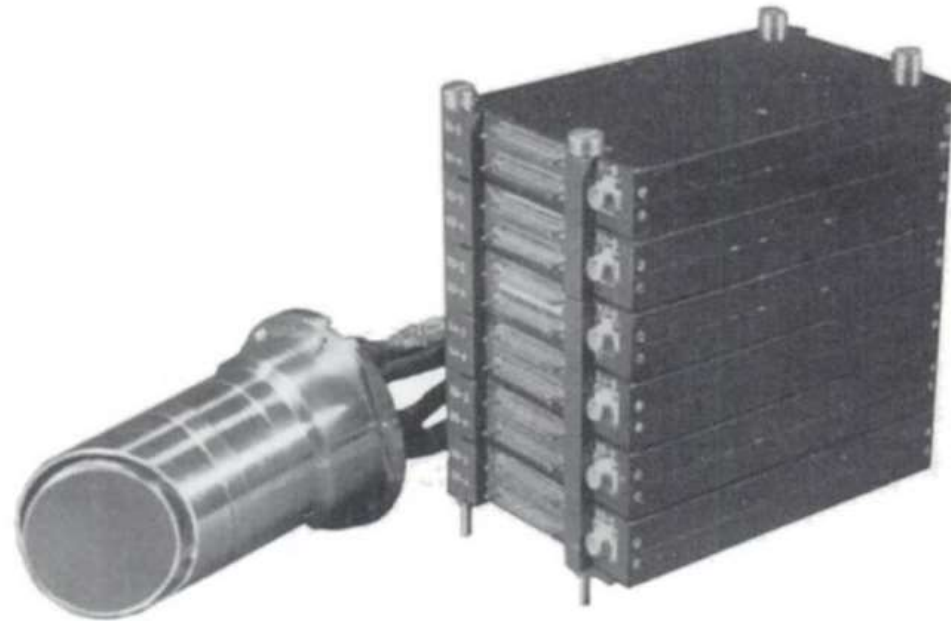
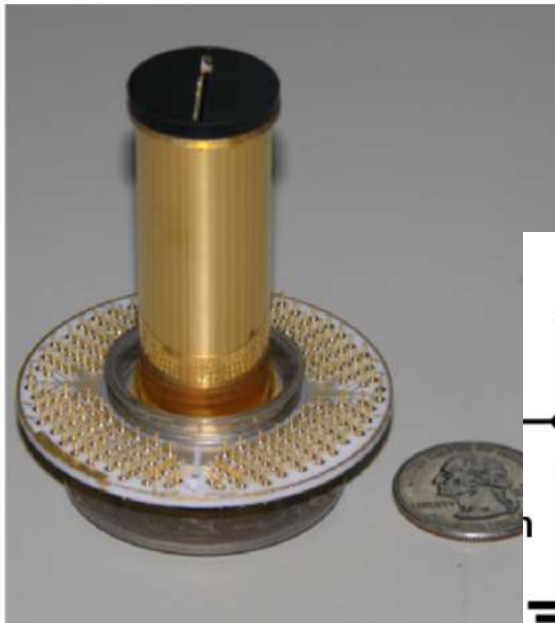
# Imaging in the Visible range

- **Very common**
  - Our eye is nicely matched to the emitted radiation of the sun
- **Imaging reflected sunlight**
  - Camera's can readily capture light and make images

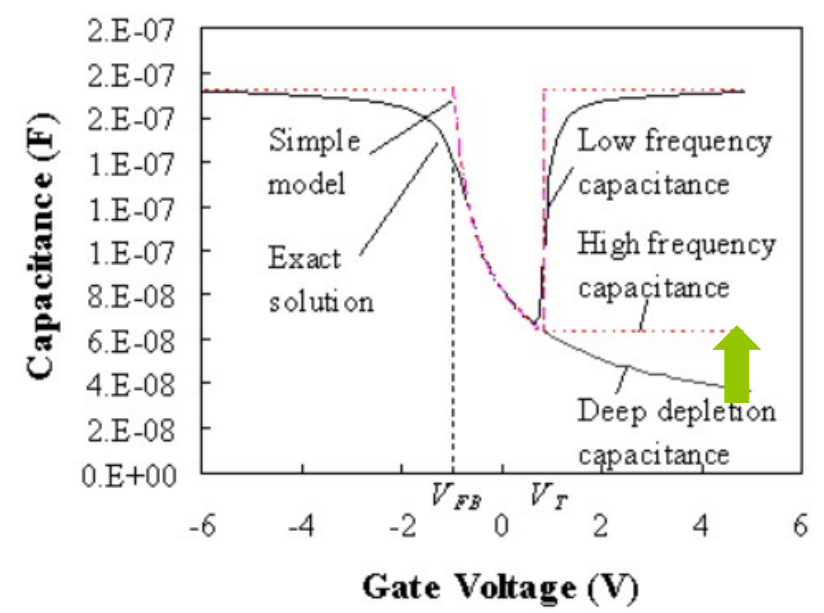
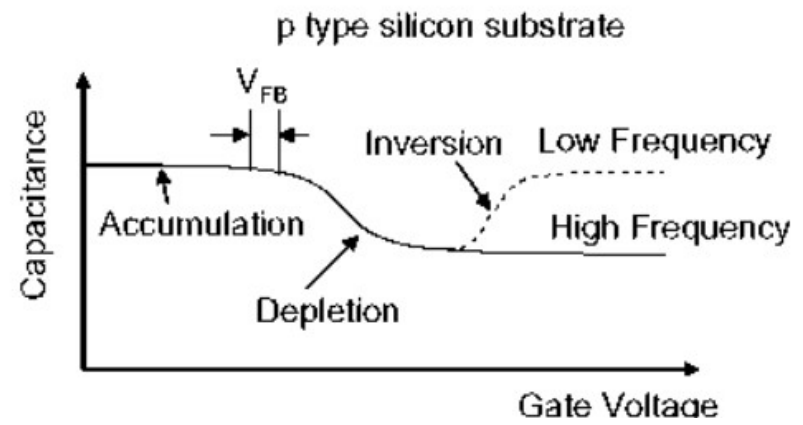
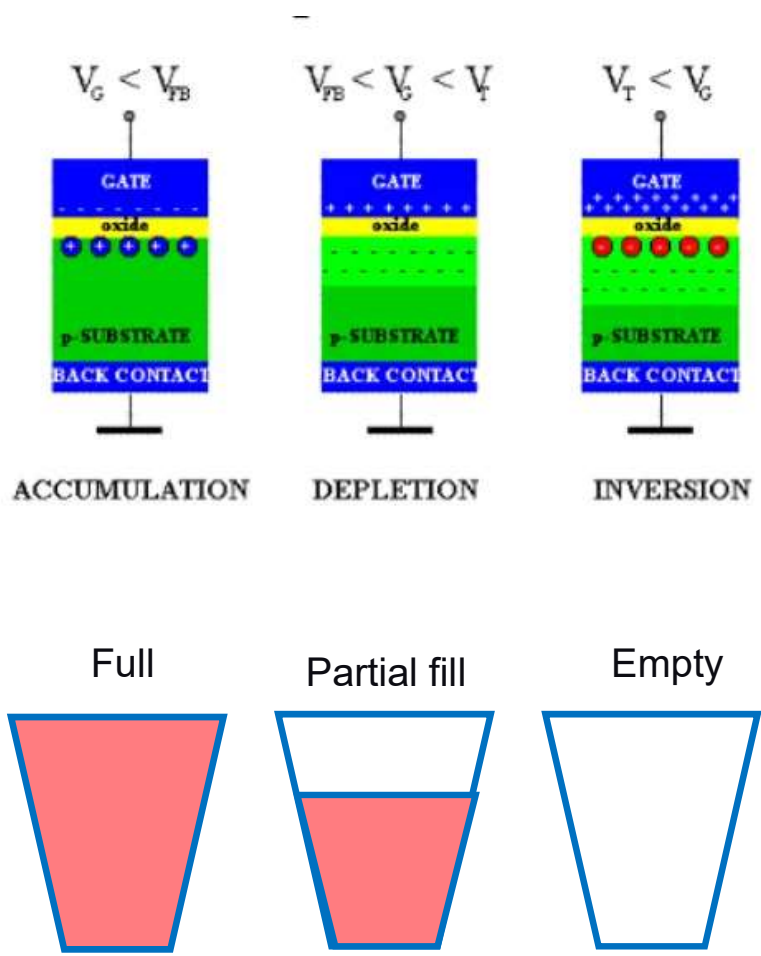




# The very start of electronic imaging



# The onsets of integration: the MOS capacitor



## CHARGE COUPLED AND CHARGE INJECTION DEVICE PERFORMANCE

### TRADEOFFS

R. D. Baertsch\*

1976

2022: still used by Thermofisher for camera's in a high radiation environment

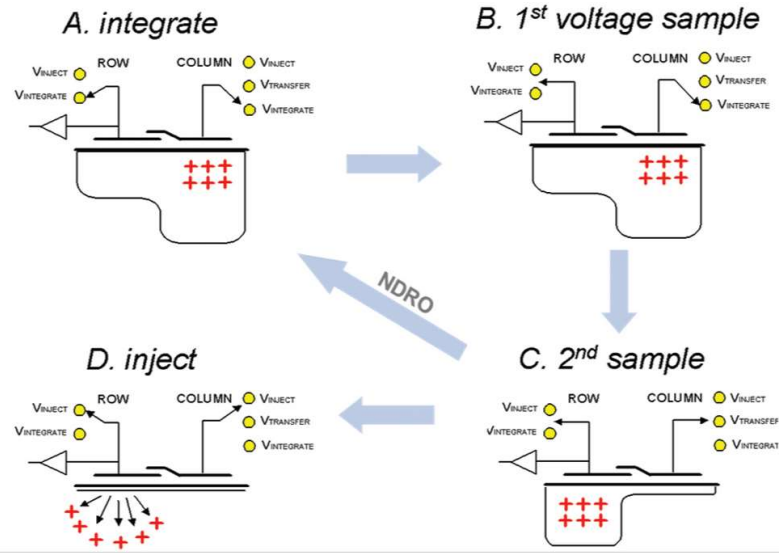
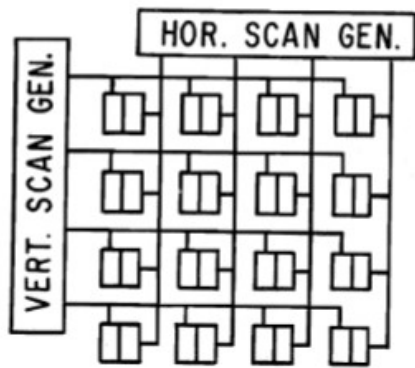
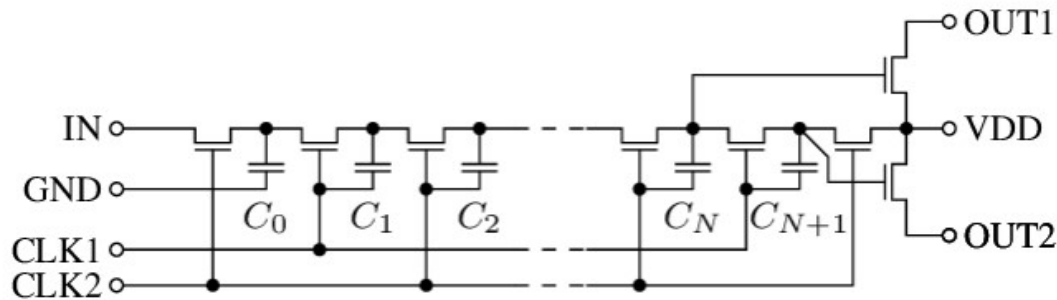
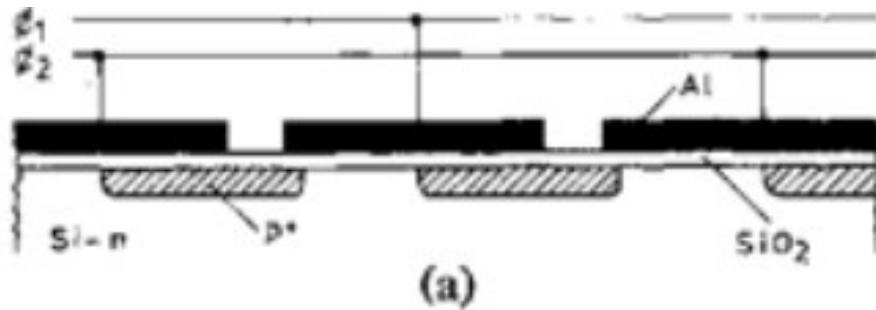


Fig. 4 - Further evaluation is required with this 244 x 248 CID imager.

# The Bucket Brigade Device



## Advantages:

- Single poly gate
- Simple process

## Disadvantages

- Not self-aligned
- Transfer losses (charge retention)

Used as delay lines:



- Caeleste company introduction
- The Historical track: towards CCD
  - Why imaging
  - The CCD precursors
  - The CCD era
  - The CCD limitations
- The Present and the future: CMOS and the application broadening

# The introduction of the CCD

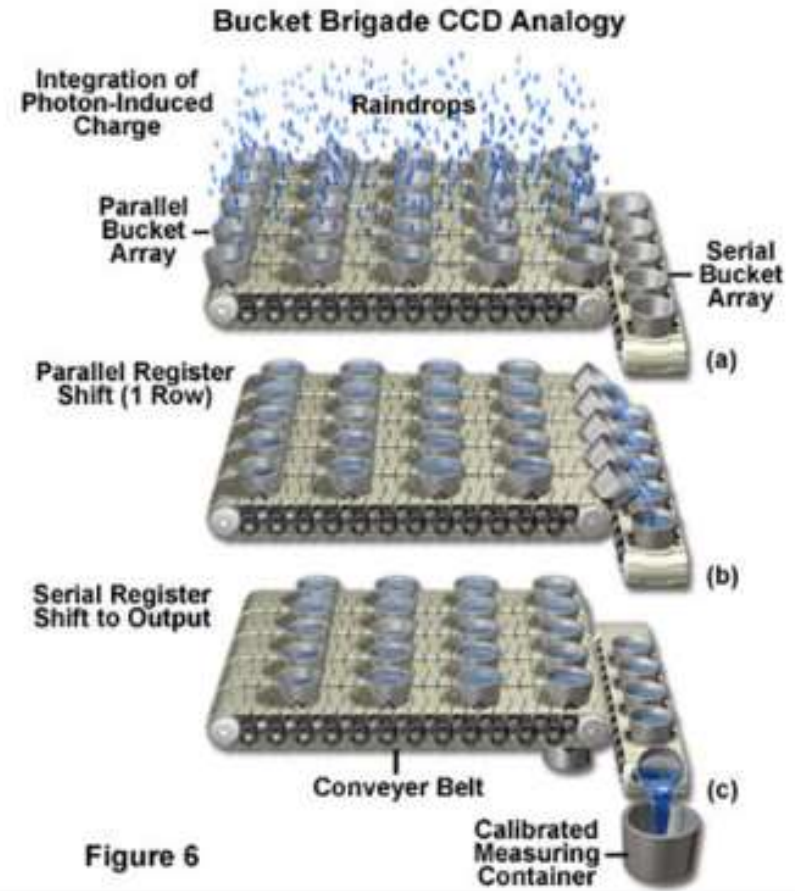
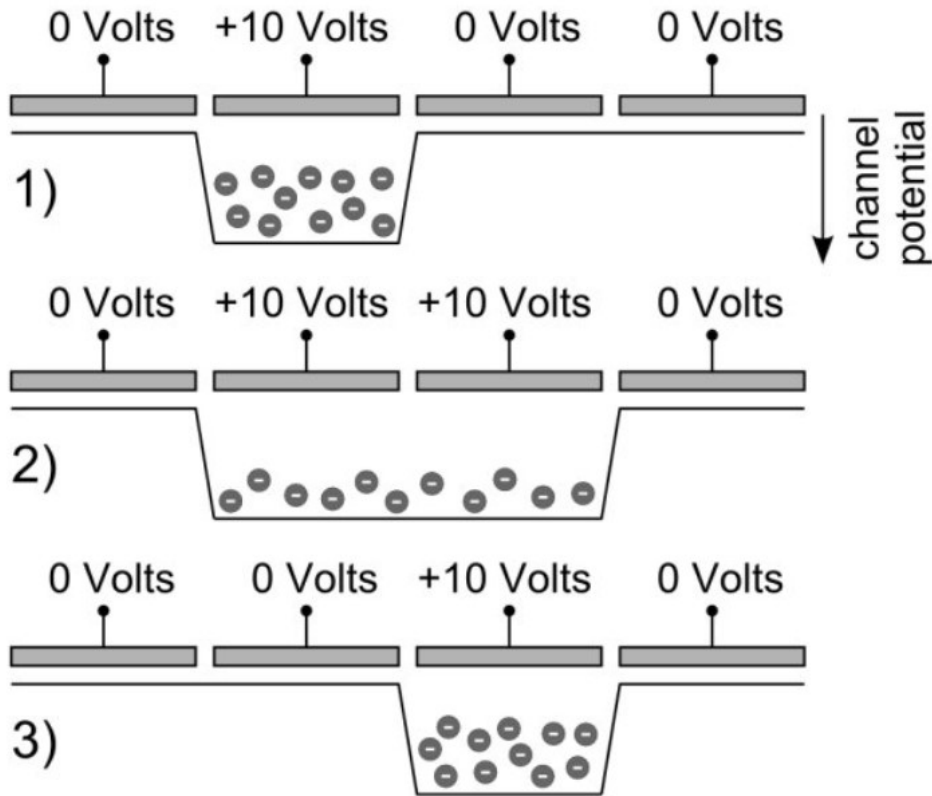
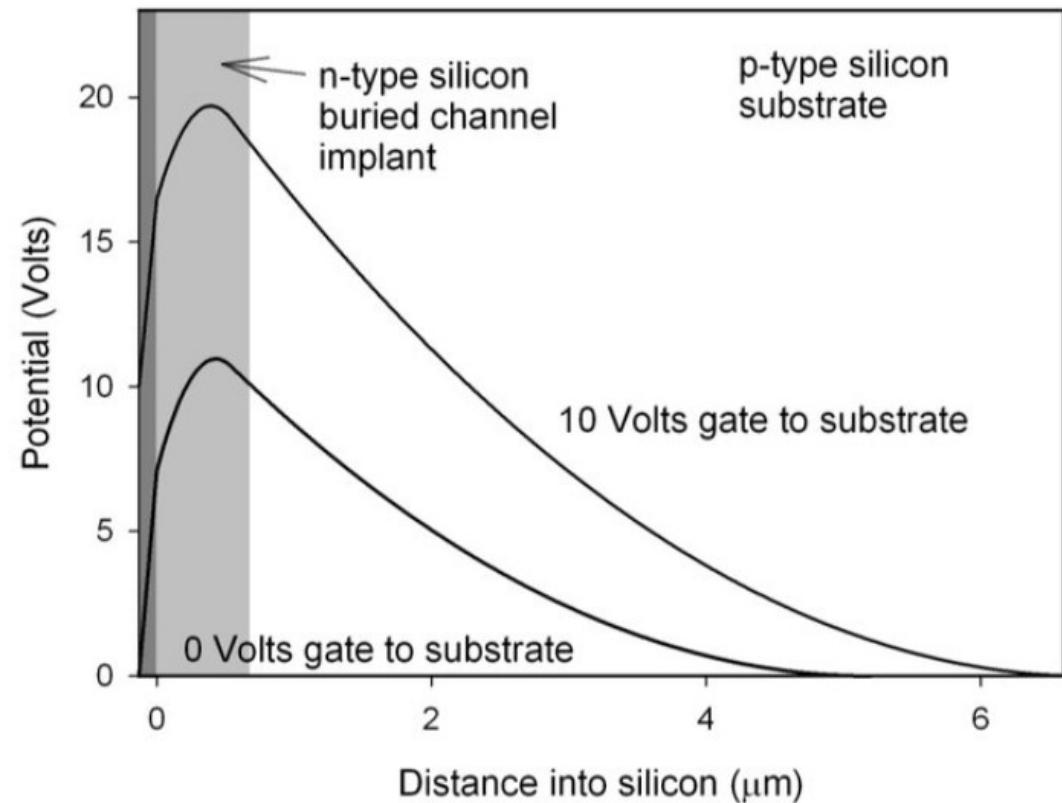
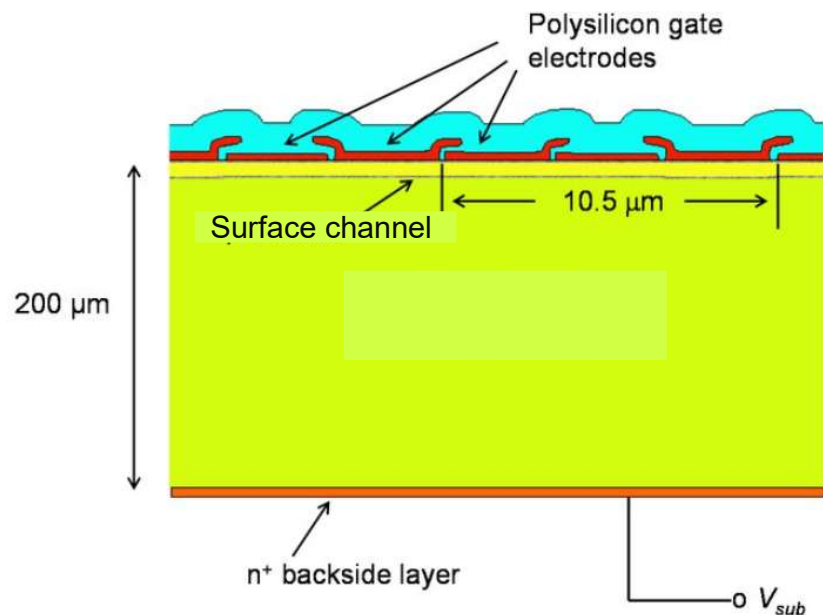


Figure 6

1969: Boyle & Smith: CCD principle  
1970 – 1972: Michael Tompsett: 1st image sensors  
1975: 1st commercial product by Eastman Kodak

# From surface channel to Buried channel

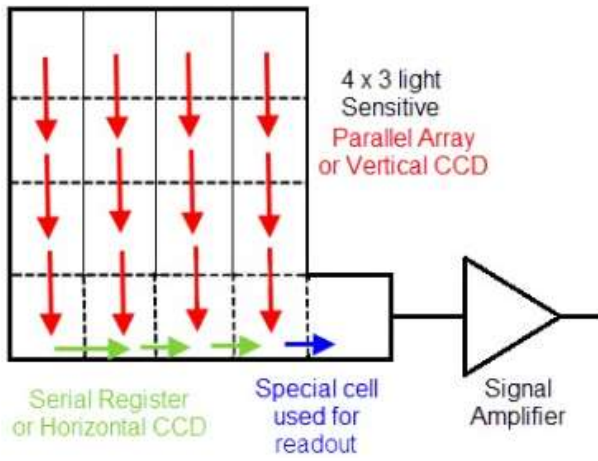


## Advantages:

- Lower dark current
- Better charge transfer
- Higher fringe fields

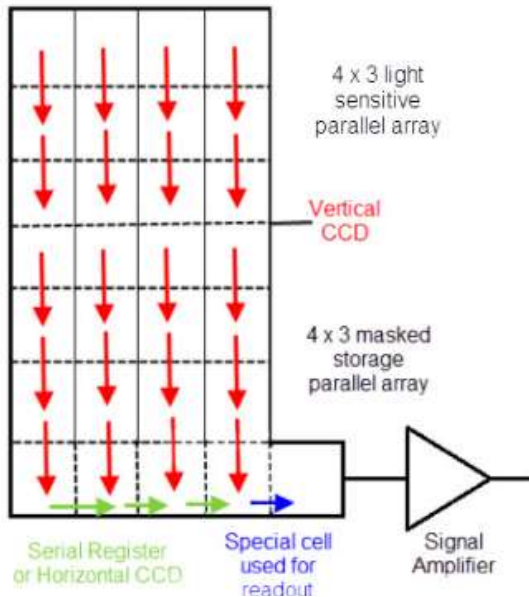
## Disadvantages

- Lower charge storage



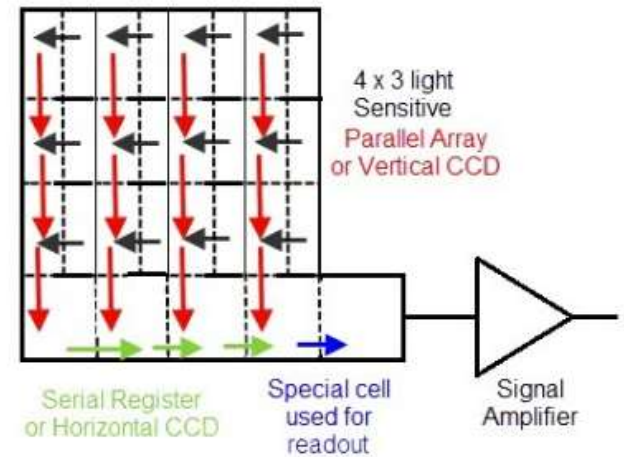
**Full Frame CCD**

- Astronomy
- Slow scan applications
- Shuttered applications
  - Still picture



**Frame transfer CCD**

- Life recording
- Easiest architecture
- Some motion blur
- Bright spot impact



**Interline transfer CCD**

- Life recording
- More complicated architecture
- Real global shutter
- No bright spot impact

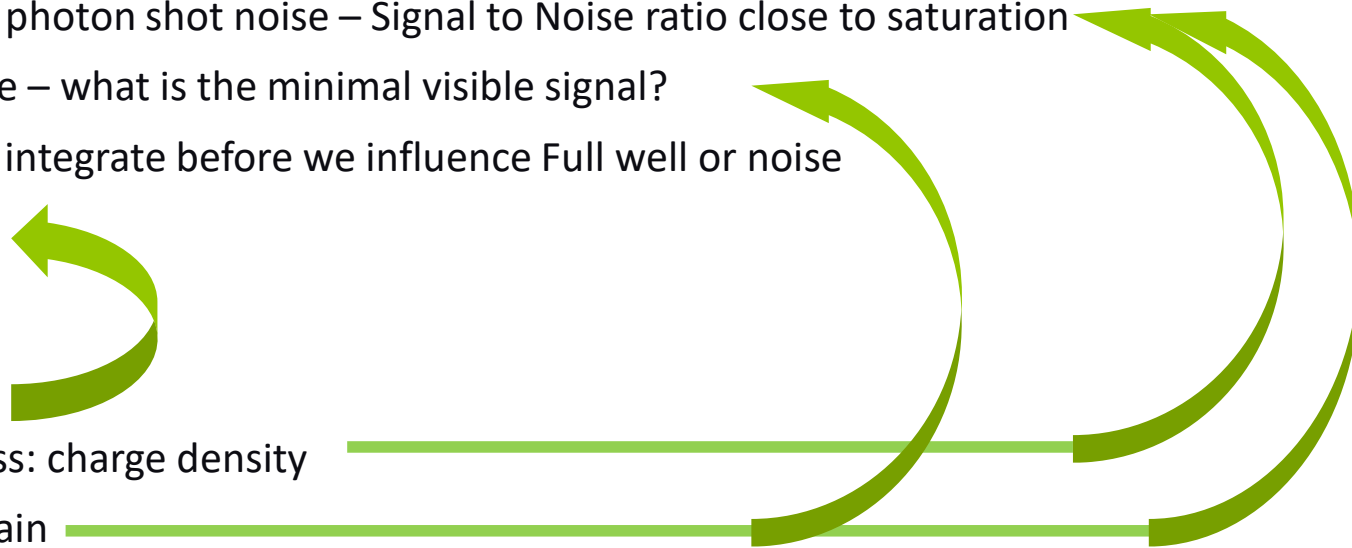


## ■ When considering an image sensor, the following performance parameters are key:

- Spectral response: collected electrons / incident photons or [A/W]
- Full well charge: related issue: photon shot noise – Signal to Noise ratio close to saturation
- Noise in dark: or Dynamic range – what is the minimal visible signal?
- Dark current: how long can we integrate before we influence Full well or noise
- Power – Current – Voltage

## ■ Some derivative parameters:

- Driving voltage – signal height
- Voltage + oxide / stack thickness: charge density
- Charge to voltage conversion gain



- Caeleste company introduction
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  - Why imaging
  - The CCD precursors
  - The CCD era
  - The CCD limitations
- The Present and the future: CMOS and the application broadening

## ■ Buried Channel CCD

- Implant condition: [1.E+12 – 2. E+12 cm<sup>-2</sup>]
- Useful “dose” = 20 %: [0.2 – 0.4E+12 cm<sup>-2</sup>] or [2000 – 4000 e-/μm<sup>2</sup>]
- Pixel size: 15 μm → storage area = 100 μm<sup>2</sup> → [200 – 400 ke-] full well → shot noise: 447 e-rms → 9 bit
- Pixel size: 5 μm → storage area = 7.5 μm<sup>2</sup> → [15 – 30 ke-] full well → shot noise: 112 e-rms → 7 bit
- Pixel size: 3 μm → storage area = 3.0 μm<sup>2</sup> → [6 – 12 ke-] full well → shot noise: 77 e-rms → 6 bit

Type	Pixel	Full well	Noise	Format	Frame rate	Type
KAF-16803	9*9 μm <sup>2</sup>	100 ke-	9e-rms	4k * 4k	1.6 Fps	Full frame
KAF-08051	5.5*5.5 μm <sup>2</sup>	20 ke-	10 e-rms	3k*2k	16 Fps	Interline
KAF-50140	4.5*4.5 μm <sup>2</sup>	13 ke-	13 e-rms	10k*4k	4 Fps	Interline
ICX829AL	8.2*8.4 μm <sup>2</sup>	50 ke-	10 e-rms	750*580	50Fps	Interline
ICX445	3.75*3.75 μm <sup>2</sup>			1.4*1k	20 Fps	Interline

## CCD

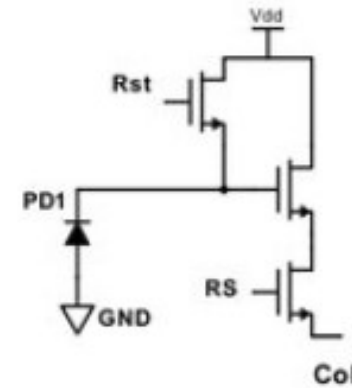
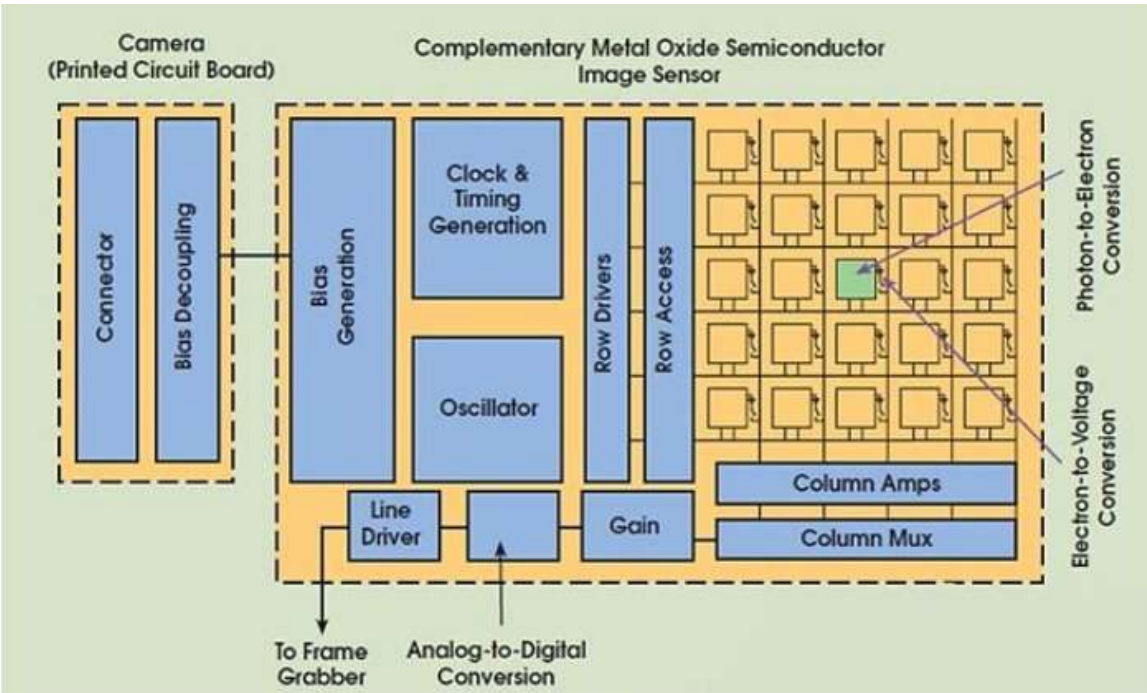
**Dedicated process - expensive**

## CMOS

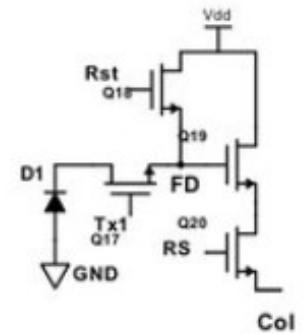
**Mainstream process – Low-cost**

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  - Basic CMOS architectures and HDR
  - CMOS tendencies and diversification
  - Non-visible imaging

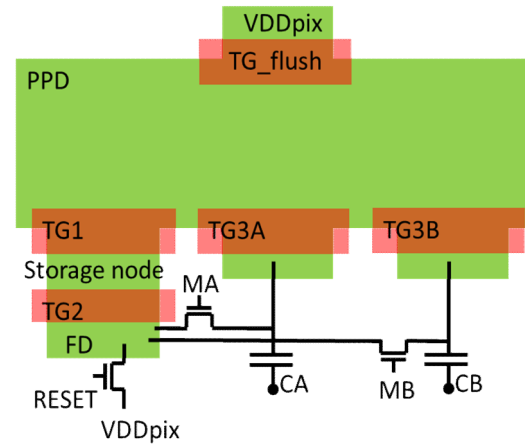
# CMOS sensor basics



a) 3T Per Pixel



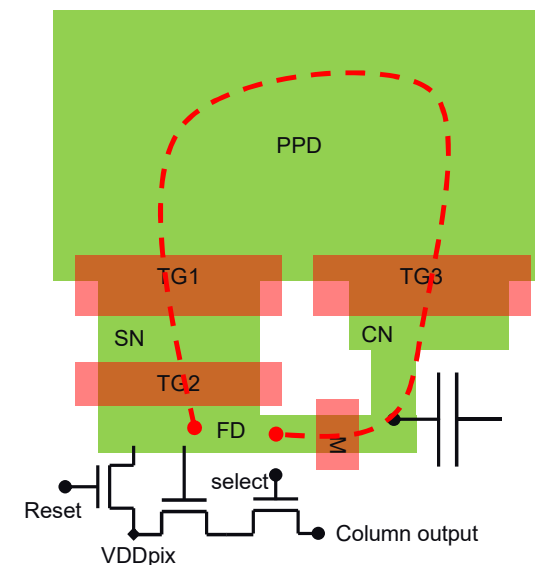
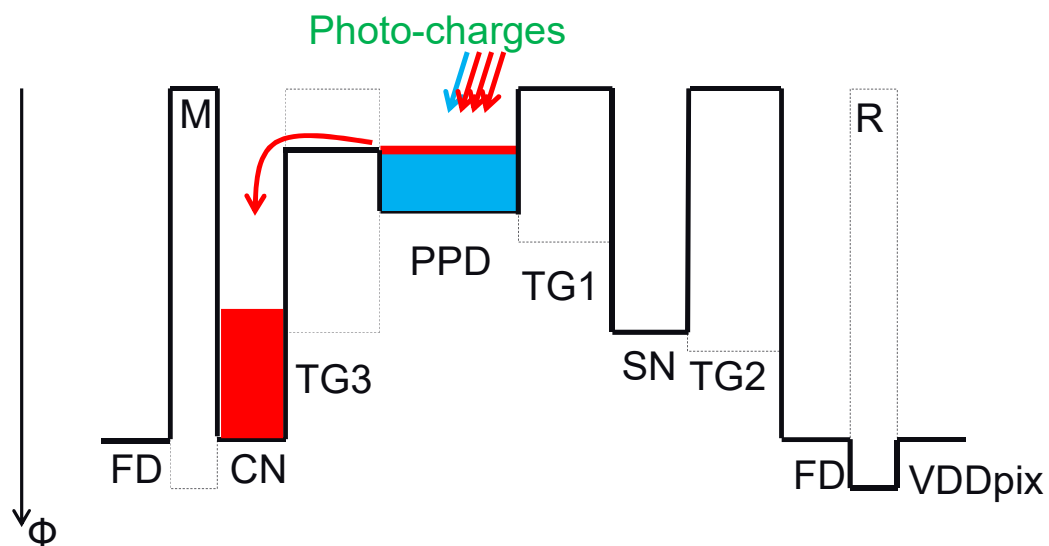
b) 4T Per Pixel



During integration photocharge is accumulated in the photodiode.  
 The TG3 gate voltage is set to the intermediate “overflow barrier” operation point.  
 When the photodiode is too full, charge overflows to the capacitor node

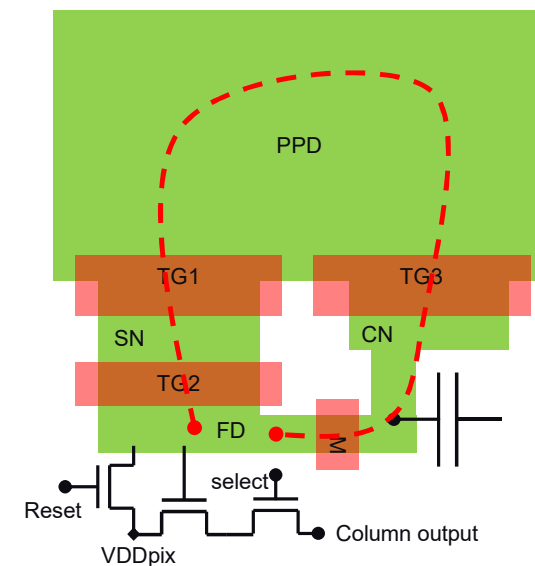
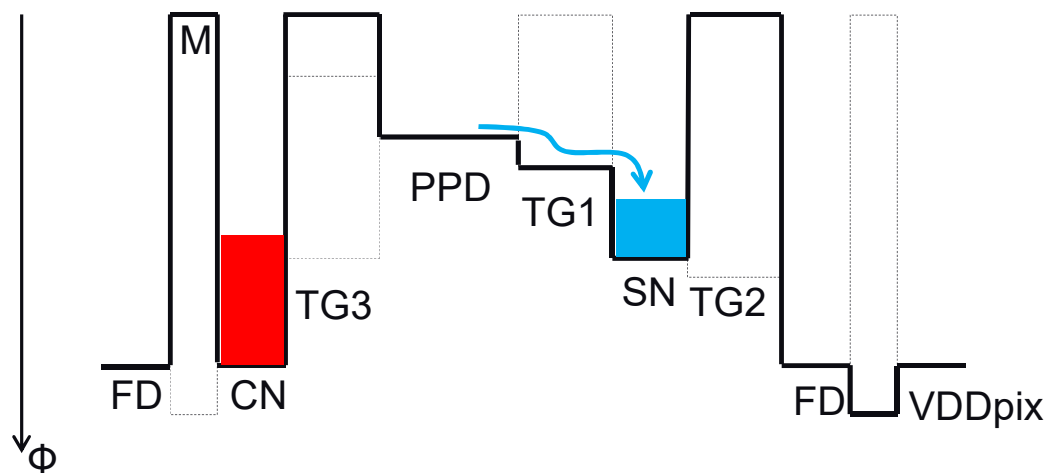
blue: charge fitting in the PPD

red: charge overflowing into the capacitor node.



End of integration time:

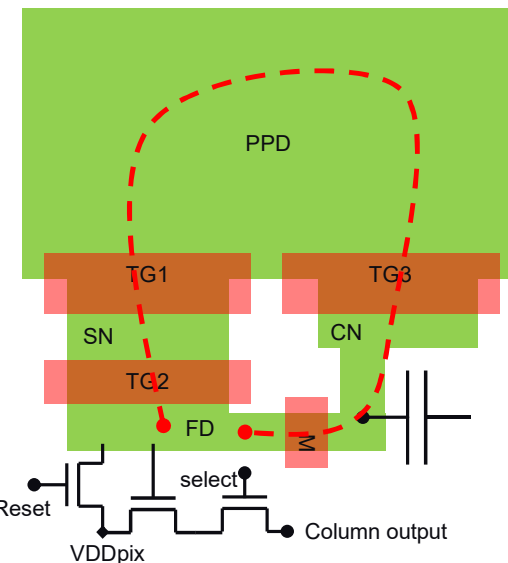
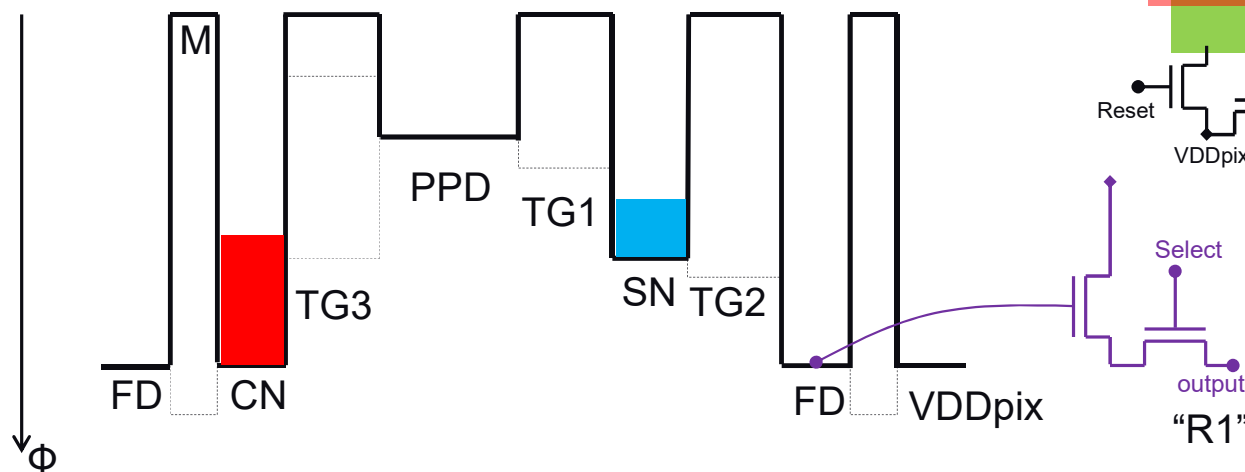
- 1) stop overflow over TG3
- 2) transfer PPD (blue) charge to the SN using TG1



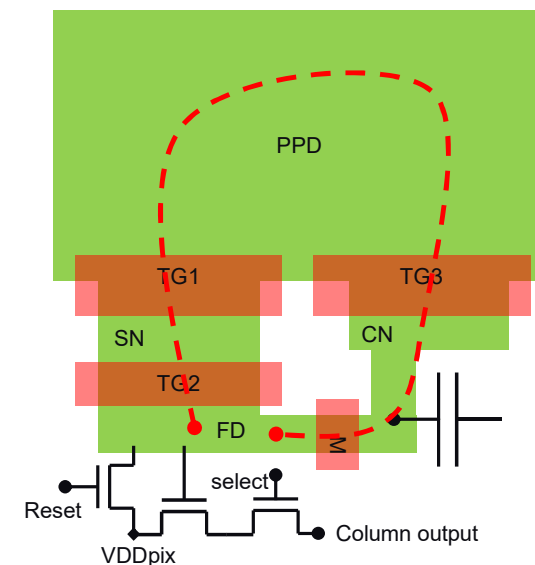
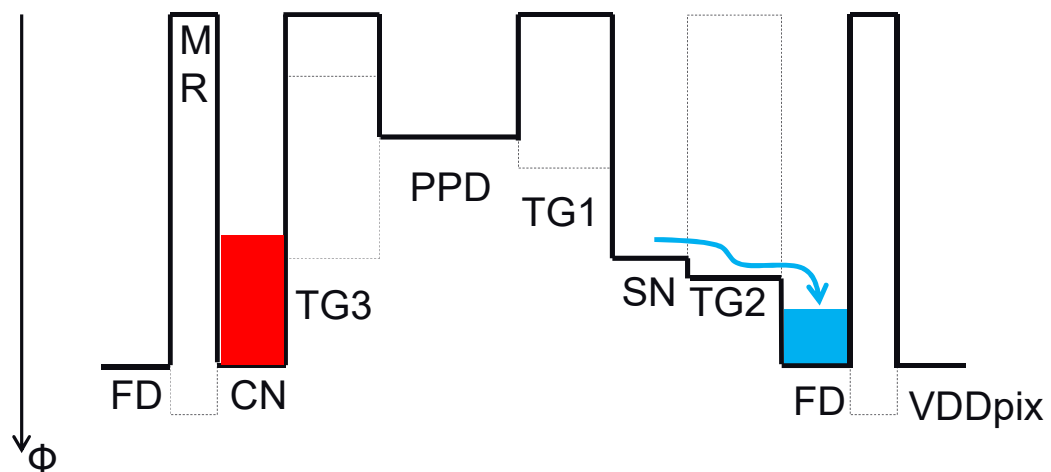


As the photocharge of the previous integration time is now available in the SN and the CN, it can be read out. The readout of the imager happens row-by-row or in “rolling readout”. The select transistors of the rows to be read out are activated, the reset transistors are turned off, and then three voltage levels are put on the column bus: “R1”, “S1” and “S2”.

“R1” is reset level as present on the FD immediately after releasing the reset.



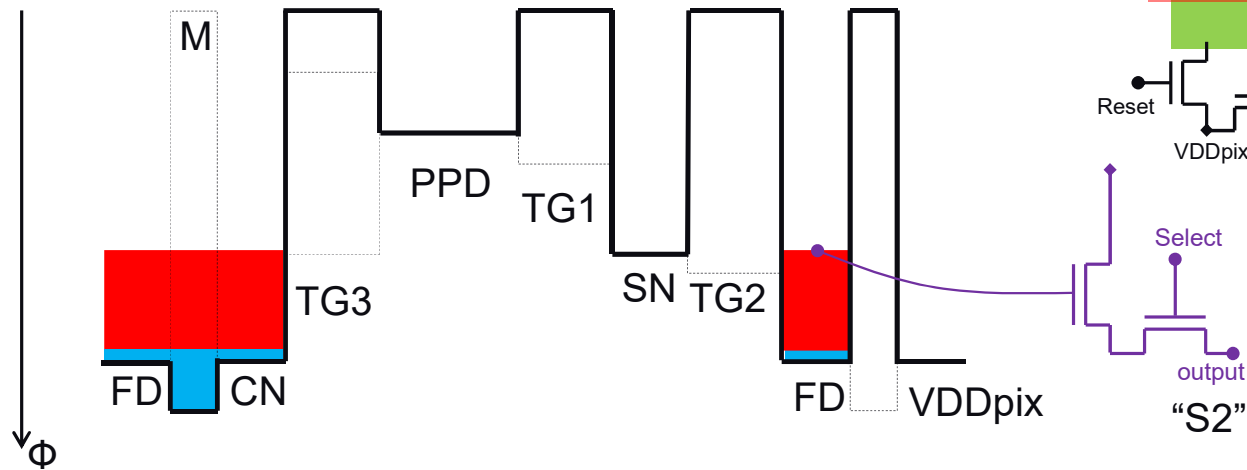
Then the gate TG2 toggled off-on-off, allowing the charge in the SN to transfer to the FD.  
 This is the "S1" signal level, representing the "blue" charge.



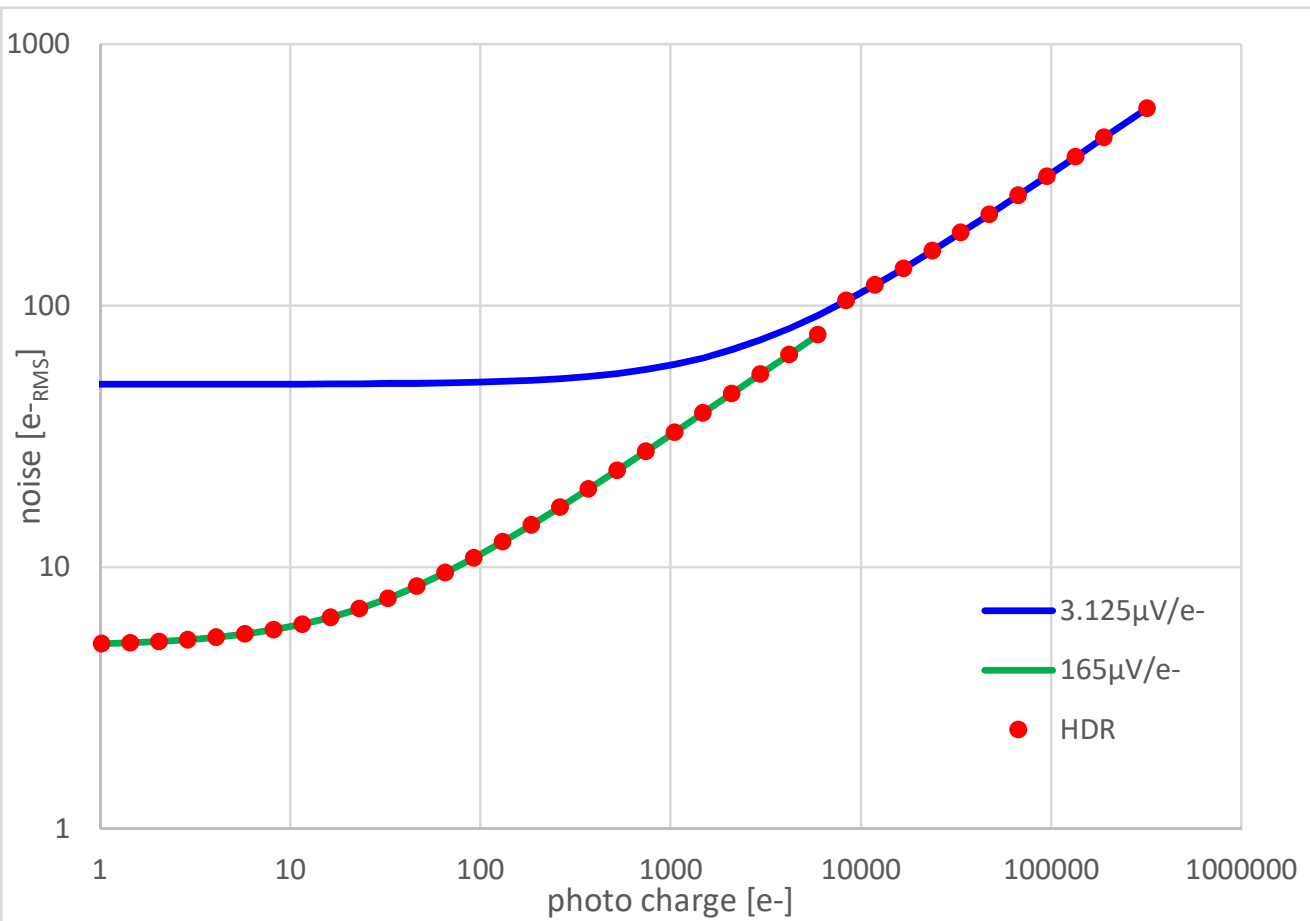
# Expertise in different applications

Then the Merge transistor is closed, shunting the FD and the CN. All photocharge, previously divided over the SN (blue) and the CN (red) is now reunited.

This signal is "S2", being the LG or high  $Q_{FW}$  signal level. We do not apply CDS on S2; still S2 is readout differentially as  $(S2-ref) \& (ref-S2)$ .



# HDR by combining two “normal” DR ranges



This graph is the “Noise versus Signal” relation of a two range image sensor pixel, i.c. the ELFIS pixel.

Each  $Q_{FW}$  range on its own has such relation. The dynamic range (DR) is defined as the ratio of the largest, near saturation, photocharge ( $Q_{FW}$ ) and the noise equivalent photocharge ( $Q_{noise}$ ) in the dark. When the two signals are combined into one “HDR” signal, it has such relation as well, and an overall dynamic range that is equal to the LG  $Q_{FW}$  divided by the HG  $Q_{noise}$ .

High  $Q_{FW}$  range:  
DR=320000/50≈6400:1

Low  $Q_{FW}$  range:  
DR=6000/6,5 ≈ 1000:1

Combination  
DR=320000/6,5 ≈ 93,8dB

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  - Basic CMOS architectures and HDR
  - CMOS tendencies and diversification
  - Non-visible imaging

**CITIUS, ALTIUS, FORTIUS**

## ■ Key specifications

- Frame rate
- Number of pixels
- Pixel size
- Noise
- Spectral response
- Quantum efficiency
- Full well

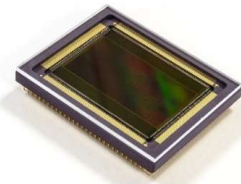
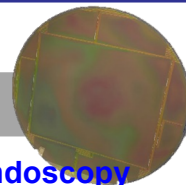
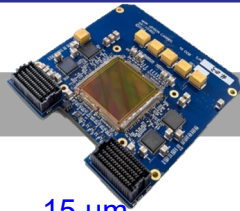
- Faster
- More pixels
- Smaller pixels
- Lower noise floor
- Better colour / NIR /UV reproduction
- Higher quantum efficiency
- Higher (but following the pixel size)

## ■ Resulting specifications

- Light sensitivity
- Dynamic range
- Bit depth

- Higher sensitivity
- Higher dynamic range
- Mainly following dynamic range

# Expertise in different applications



CMOS  
Image sensor  
Diversity

## Scientific & Space

### High sensitivity devices

Medium – large pixels: 5.5 ... 9 ... 12 ... 15  $\mu\text{m}$   
Larger formats  
high cost  
FW: up to 400 000 e-  
Noise: 1 - 2 e-rms  
Long Tint = lower power

## Medical & Life science

### Xray

Large pixels: 100  $\mu\text{m}$   
Up to Wafer scale  
Low cost  
FW:  $\pm$  100 000 e-  
Noise:  $\pm$  10 e-rms

### Endoscopy

small pixels: 1.12  $\mu\text{m}$   
1..3 mm size  
1 wafer lot = life time  
FW: 10 000 e-  
Noise:  $\pm$  2 e-rms

## Industrial applications

### High Speed devices

Medium large pixels: 5.5 ... 9 ... 12 ... 15  $\mu\text{m}$   
Larger formats  
Medium cost – high speed  
FW: up to 400 000 e-  
Noise: 1 - 2 e-rms  
Short Tint = higher power

## Consumer

### Mobile phone – Security

Smaller pixels: 2.5 ... 1.4 ... 1.12 ... 0.8  $\mu\text{m}$   
Smaller outline  
Low cost  
FW: 5 000 – 10 000 e-  
Noise: 2 -5 e-rms

## ■ Key specifications

- Frame rate → **Faster**
- Number of pixels → **More pixels**  
Smaller pixels
- Pixel size → **Lower noise floor**
- Noise → **Lower noise floor**
- Spectral response → Better colour / **NIR / UV / Xray / Low cost IR**
- Quantum efficiency → **Higher quantum efficiency**
- Full well → **Higher** ← → **Higher gain**

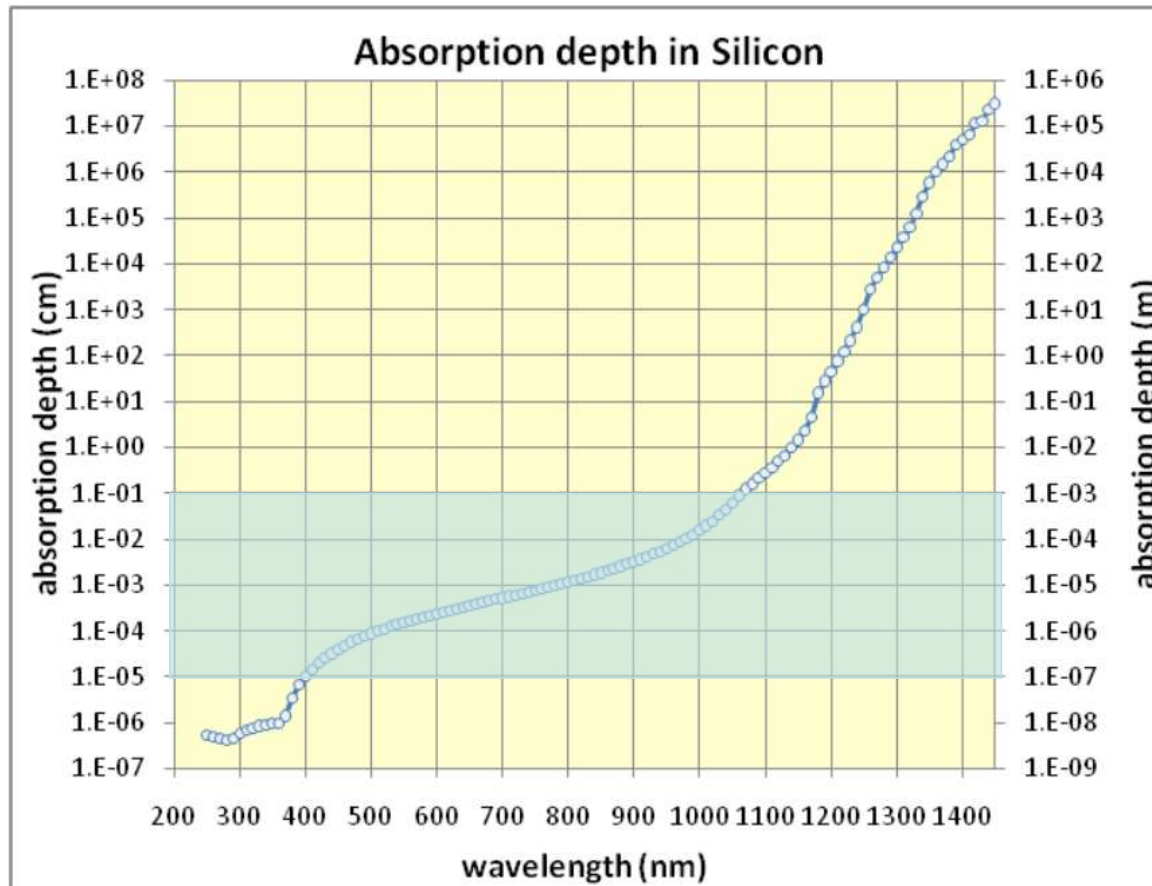
## ■ Resulting specifications

- Light sensitivity → Higher sensitivity
- Dynamic range → Higher dynamic range
- Bit depth → Mainly following dynamic range
- Large format → **Stitched designs**
- Temperature range → **Cooled Operation**

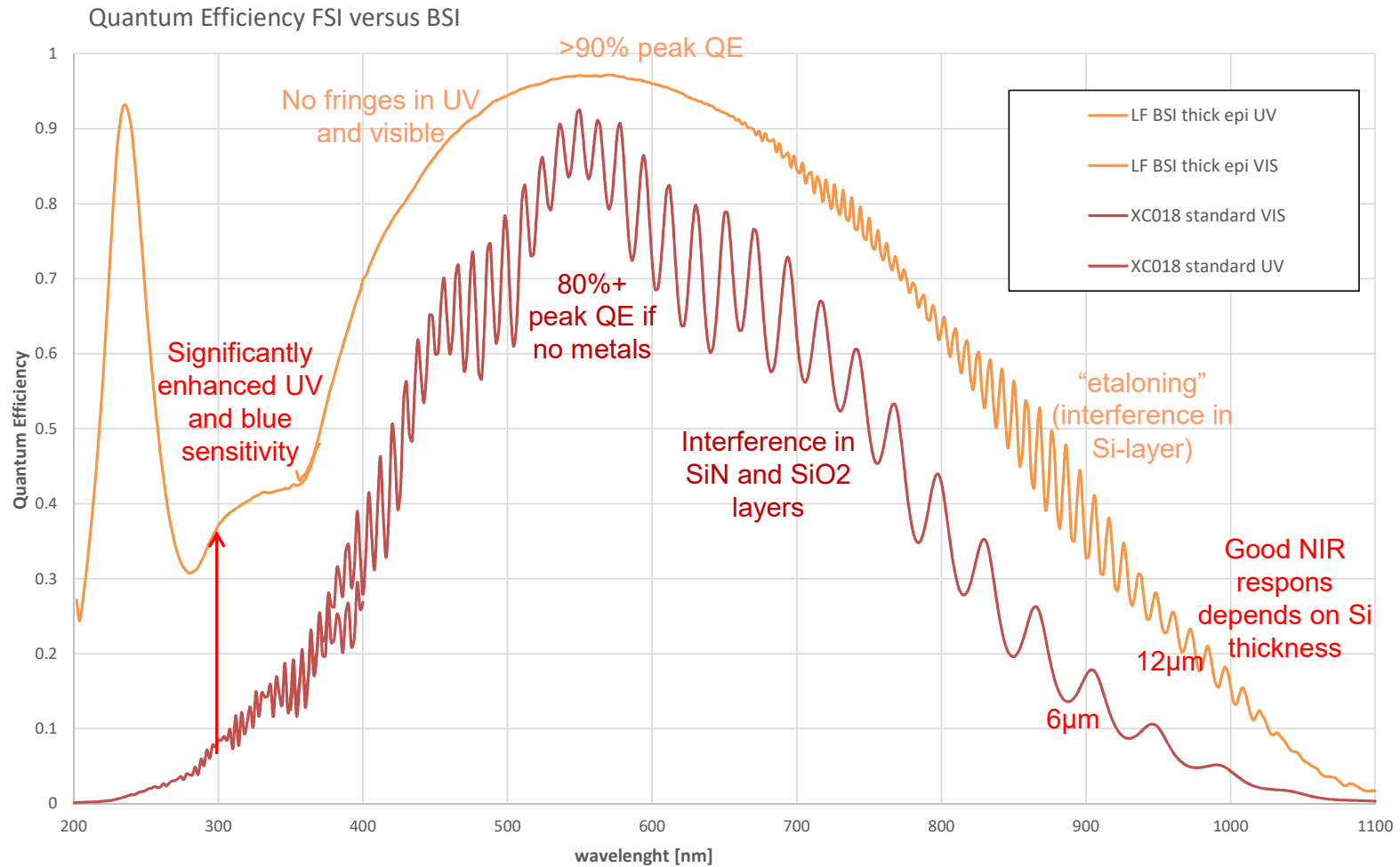


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# Where is the light absorbed

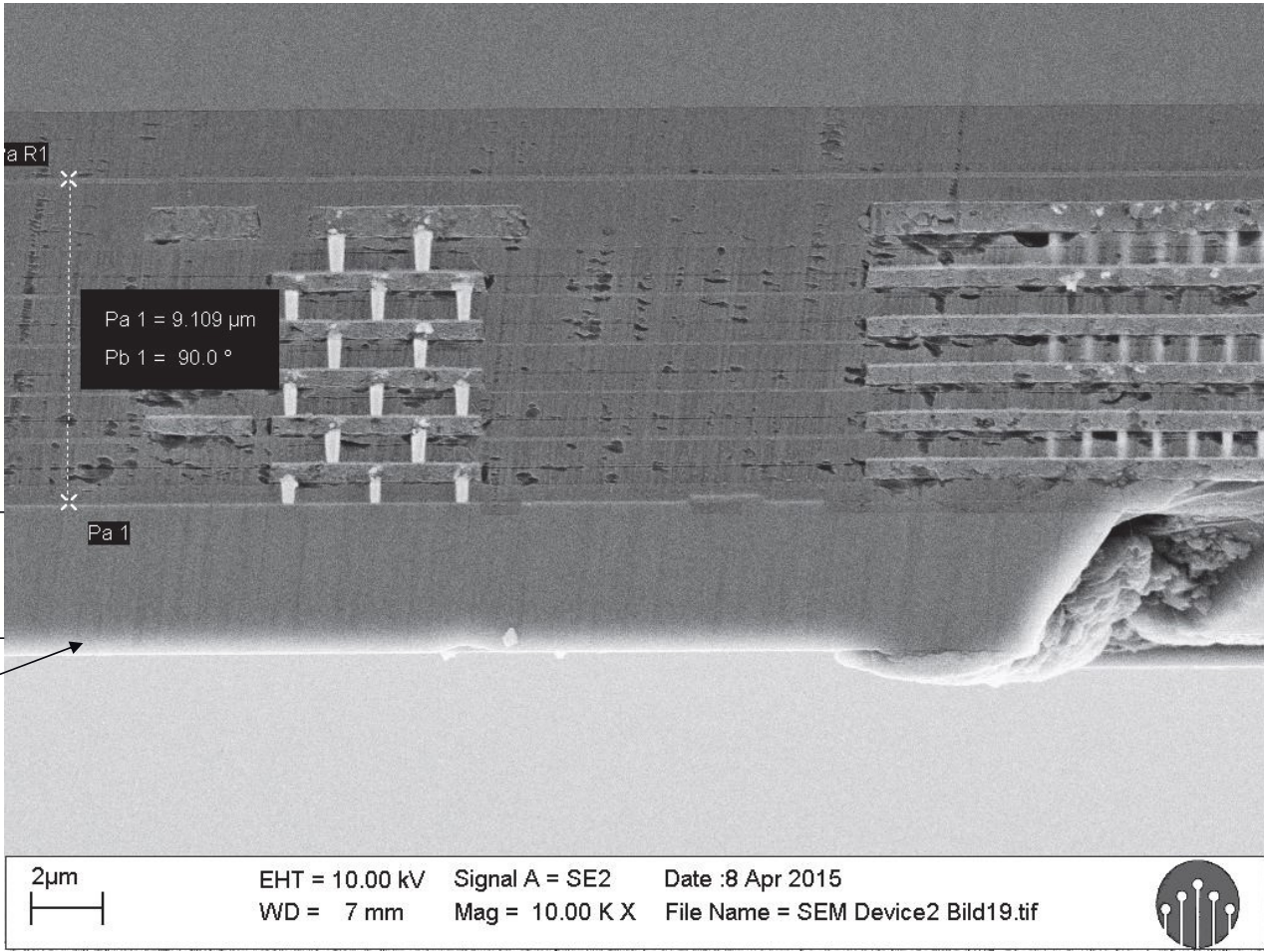
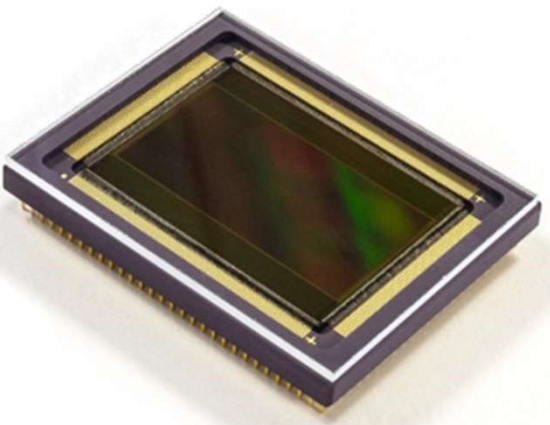


# BSI versus FSI: QE



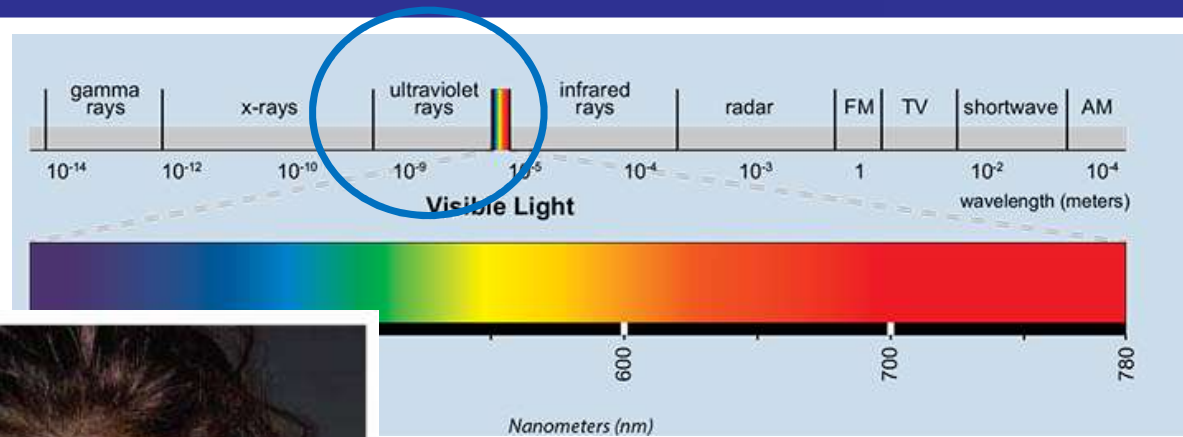
## SEM Cross Section

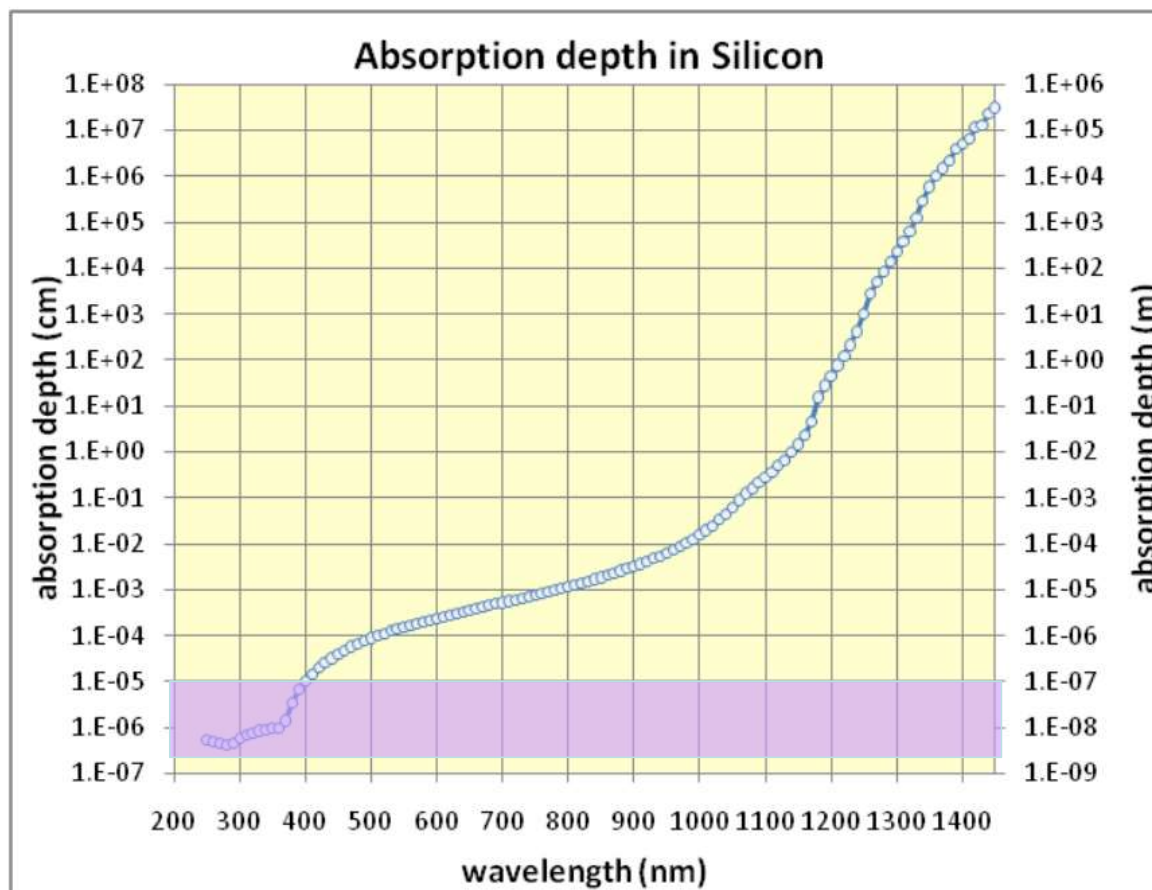
Carrier Wafer



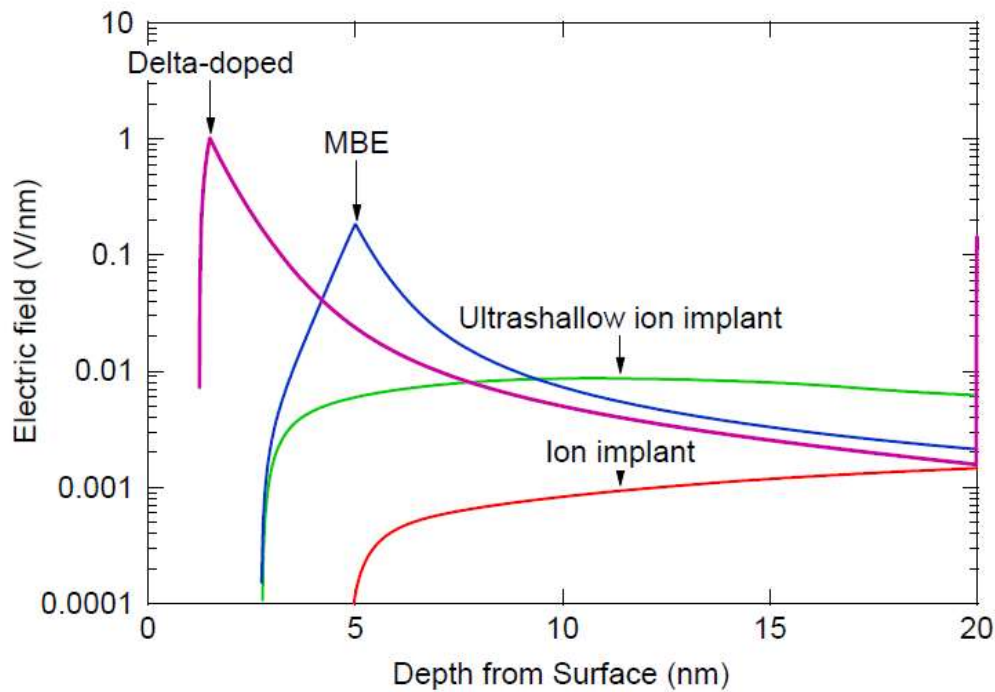
# Why using other wavelengths

- Different view on objects
- Skin inspection





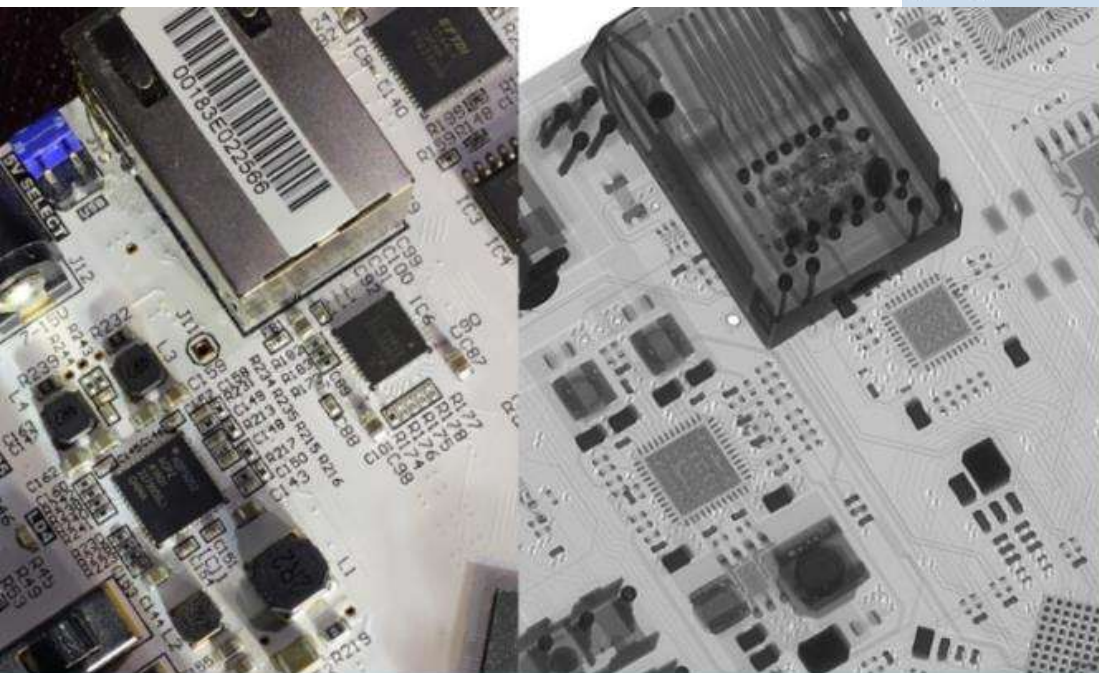
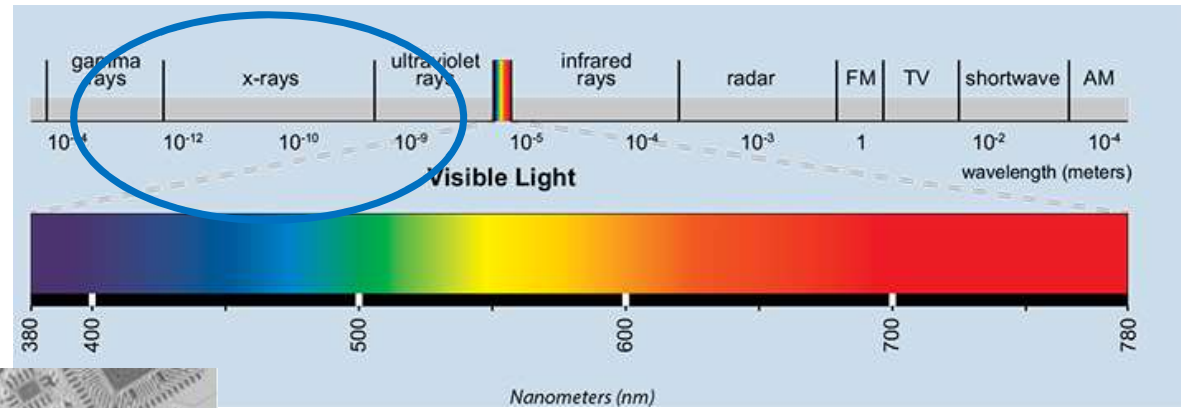
## ELECTRIC FIELD



Good surface uniformity  
Low scattering  
Very shallow back-surface field

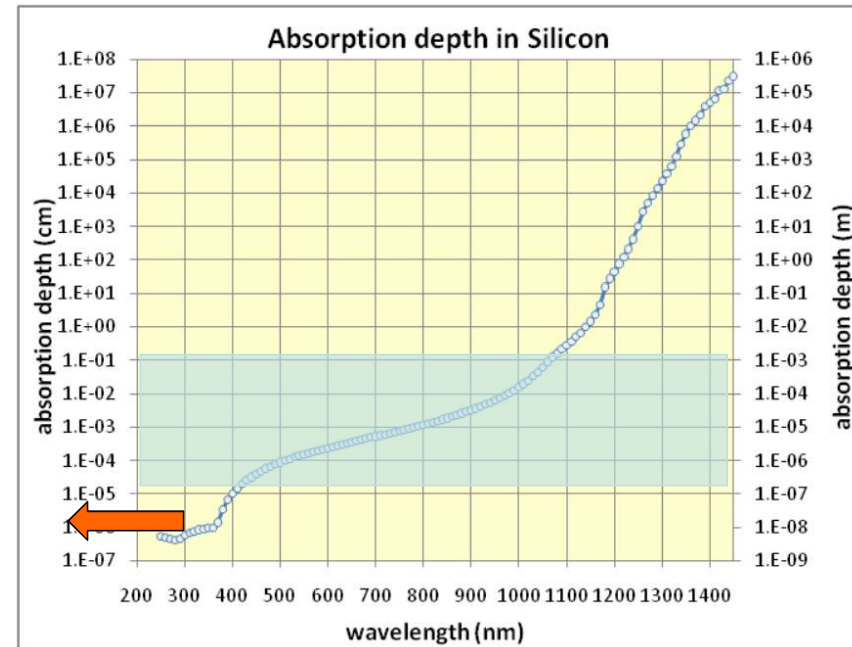
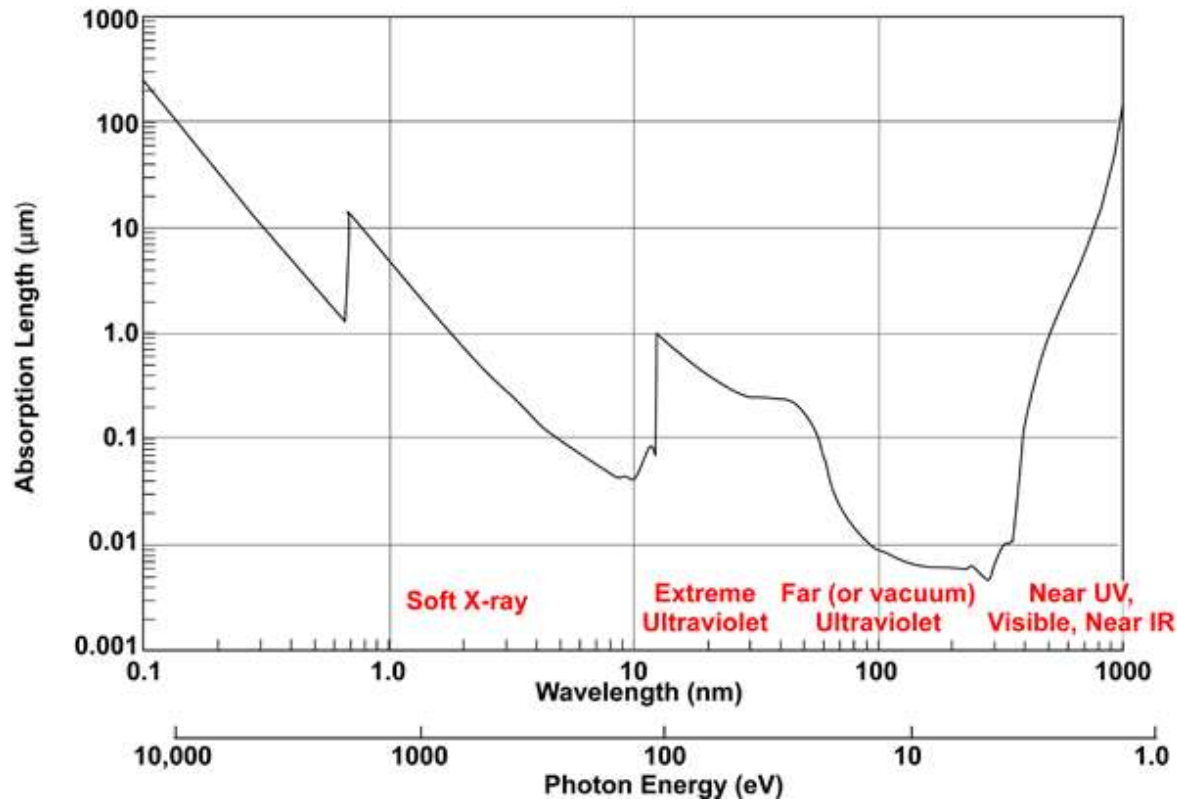
# Why using other wavelengths

- Different view on objects
- Xray PCB inspection

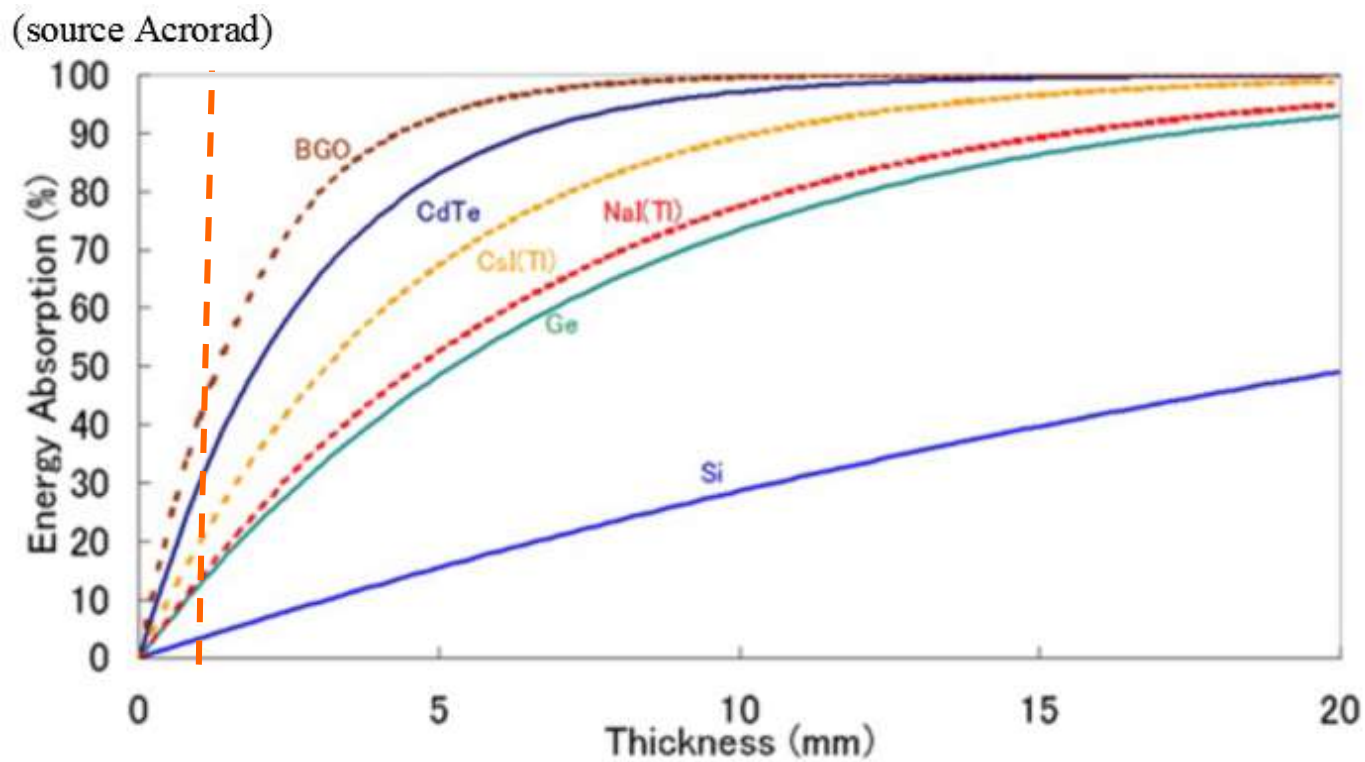




# Absorption of X-rays

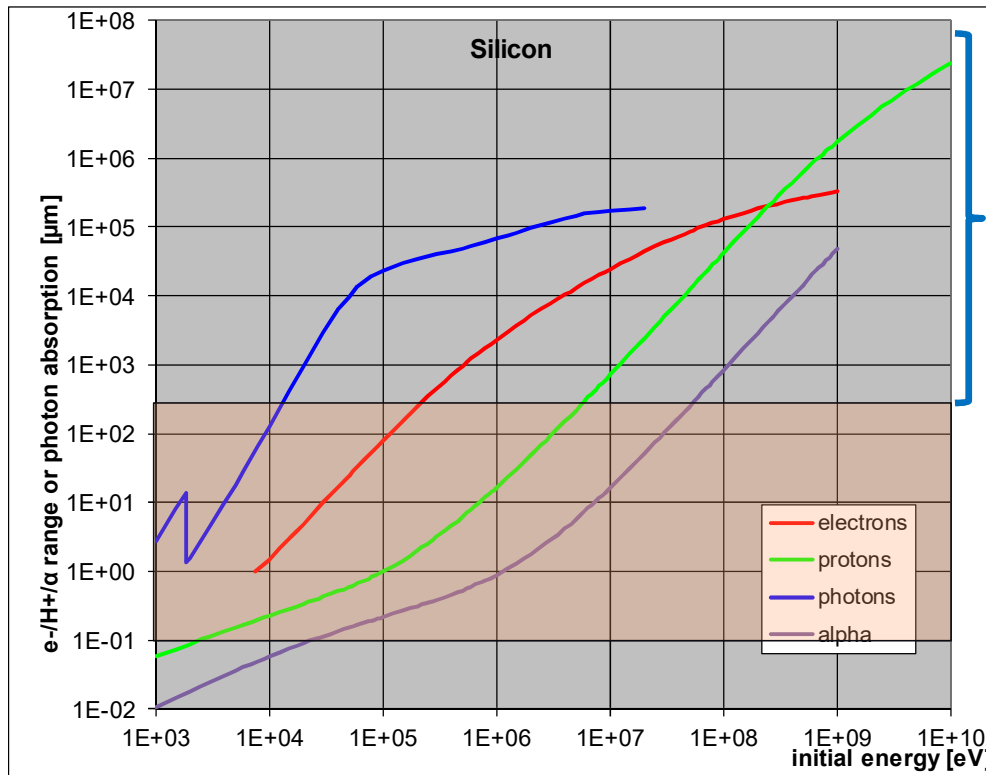


# X-ray require heavy materials







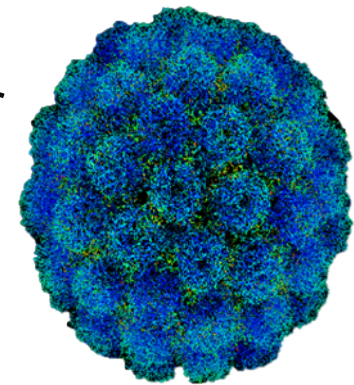


## Energy resolving

- Use of scintillator
- On Fiber-optic faceplate
- Directly on surface

## Trajectory

- Only presence detection
- No scintillator necessary



- **CCD have seen an incredible growth between 1980 – 2010**
- **CCD will be gradually phased out**
  - Small community
  - Technology (un)availability
  - Pixel size
  - Performance
  - Last buys are ongoing at various places
  - Last bastion: scientific imaging
- **CMOS images are (becoming) mainstream**
  - Large Community
  - Open foundry model
  - High degree of integration, even 3D integration potential
  - Faster read-out, lower noise
  - Uniformity is becoming better